

Amendments to the Claims:

Please cancel claims 16, 17 and 21 without prejudice or disclaimer of the subject matter contained therein.

This listing of claims will replace all prior versions, and listings, of claims in the application:

Listing of Claims:

Claims 1 - 11 (canceled)

12. (previously presented) A plasma processing apparatus for processing a product using plasma, comprising:

a power source for applying bias power to an electrode on which a substrate to be processed is disposed;

an insulating layer formed on a surface of said electrode on which said substrate to be processed is disposed;

a first conductive material buried within and surrounded by said insulating layer in a ring-like form;

a first feeder line connecting said power source and said first conductive material buried within said insulating layer;

a first variable capacitor provided in said first feeder line;

a silicon ring mounted at a position surrounding the substrate to be processed, on the surface of said electrode on which the substrate to be processed is disposed;

a second conductive material buried within and surrounded by said insulating layer and under said silicon ring;

a second feeder line connecting said power source and said second conductive material buried within said insulating layer; and

a second variable capacitor provided in said second feeder line;

wherein one portion of said insulating layer formed on an outer part of said electrode where said first conductive material and said second conductive material are buried within and surrounded by said insulating layer has a thickness which is greater than a thickness of another portion of said insulating layer where said first conductive material and said second conductive material are not buried and which extends from a central part of said electrode to the one portion of said insulating layer where said first conductive material and said second conductive material are buried.

13. (previously presented) The apparatus according to claim 12, wherein said insulating layer formed on the surface of said electrode includes alumina.

Claim 14 (canceled)

15. (previously presented) The apparatus according to claim 12, wherein the one portion of said insulating layer is formed on said first conductive material and said second conductive material, between said first conductive material and said electrode, and between said second conductive material and said electrode so as to surround said first conductive material and said second conductive material, and the another portion of said insulating layer is formed at the central part of said electrode where said first conductive material and said second conductive material are not buried.

Claims 16 and 17 (canceled)

18. (previously presented) The apparatus according to claim 12, wherein said insulating layer at the one portion where said first conductive material is formed has three times the thickness of said another portion of said insulating layer.

19. (previously presented) The apparatus according to claim 12, wherein said insulating layer at the one portion where said second conductive material is formed has two times the thickness of said another portion of said insulating layer.

20. (previously presented) The apparatus according to claim 12, wherein said another portion of said insulating layer has a substantially constant thickness.

Claim 21 (canceled)